## **Development of An 0.2eV Energy Resolution Analytical Electron Microscope**

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We developed a high energy-resolution electron energy-loss spectroscopy (EELS) microscope (JEM-HREA80) to investigate detailed electronic structures of materials [1,2]. The microscope is equipped with an octapole-type Wien-filter monochromator and analyzer. The energy and spatial resolutions were 50meV-0.2eV and 30-100nm in diameter, respectively. On the other hand, we developed an  $\Omega$ -filter electron microscope (JEM-2010FEF), which enables us to perform precise crystal structure refinement in a sub-nanometer scale using the CBED method [3,4]. Since it does not have a monochromator, its energy resolution of EELS spectra remains at about 1eV, which is not sufficient for the detailed study of electronic structures of materials.

We have started to manufacture a new 200kV electron microscope under a project "MIRAI-21", which enables us to investigate both crystal- and electronic-structures of advanced materials in nanometer scale areas [5]. MIRAI means "Future" in Japanese and the abbreviation of Microscope for Innovative Research and Advanced Investigation. The microscope has a point resolution of 0.19nm and an energy resolution of 0.2eV at a less than 2nm diameter probe. In this paper, the basic design of the microscope and the test result of the monochromator are reported.

Figure 1 shows the appearance of the MIRAI-21 microscope. This microscope is constructed based on the JEM-2010FEF, and equipped with a newly developed Wien-filter monochromator and an improved  $\Omega$ -filter analyzer. The monochromator is located between the extraction anode for the ZrO/W emitter and the acceleration tube. The monochromator consists of two octapole-type Wien-filters (Fig.2) and an energy-selection slit, which exists between the two filters. . Astigmatic focus is used to reduce the Boersch effect, as shown in Fig. 3. The filter 1 (WF1) disperses the incident electron beam and forms a line-focused image on the energy selection slit. The filter 2 (WF2) cancels out the energy dispersion of WF1 and forms a stigmatic electron beam at the exit of the monochromator.

The basic performance of the monochromator was tested using a remodeled 120kV-type electron microscope with a LaB<sub>6</sub> filament. Figure 4(a) shows the astigmatic beam shape, which elongated in the direction, perpendicular to the energy-dispersion direction at the energy-dispersion plane (the slit position). The electron beam energy ingoing to the monochromator was 800eV. The electron beam was shifted about 70µm by a 4eV change of the electron-beam energy. Thus, the energy dispersion was about 17μm/eV. Figure 4(b) shows the electron-beam shape at the exit of the monochromator under the same incident beam condition as Fig.4 (a). It should be noted that the beam has an almost round shape.

The present study is supported by a project "Technology Transfer D98-04" of Japan Science and Technology Corporation. (JST).

## References

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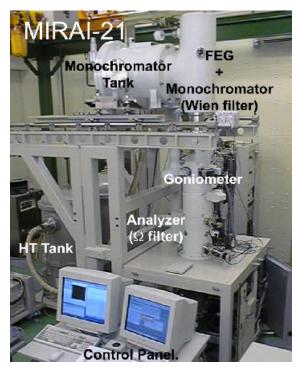


FIG. 1. Appearance of MIRAI-21

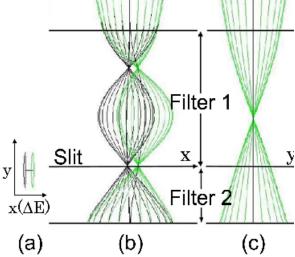


FIG. 3. (a) Beam shape on the slit. (b) Ray-path in dispersion direction (X-Z). (c) Ray-path in non-dispersion direction (Y-Z).

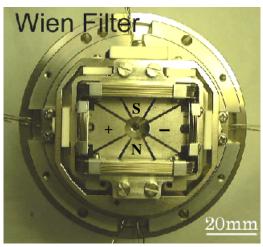


FIG. 2. Octapole-type Wien filter

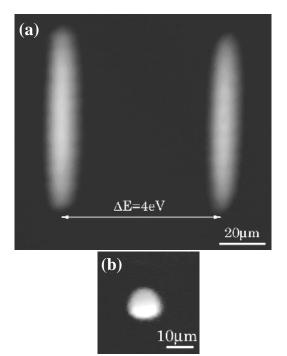


FIG. 4. (a) Astigmatic beam shape on the slit with an energy dispersion of about 17  $\mu$ m/eV. (b) Stigmatic beam shape at the exit of the monochromator.